

## OS3: The Third International Symposium on Integrated Flow Science IV Advanced Semiconductor and Digital Transformation

November 12, 2025

EX-3A

- OS3-1            **Synthesis and Properties of Group IV Clathrate Thin Film** (*Invited*)  
9:00-9:30        Tetsuji Kume, Fumitaka Ohashi, Himanshu S. Jha (Gifu University, Japan)
- OS3-2            **Pulse Response of Ag<sub>2</sub>S Resistance Change Device**  
9:30-9:45        Kosei Hamada, Takeo Ohno (Oita University, Japan), Kazuhiko Endo (Tohoku University, Japan)
- OS3-3            **The Modeling and Heat Transfer Analysis in RRAM Devices**  
9:45-10:00       Aldo Marcelino, Hsin-Yi Shih (Chang Gung University, Taiwan), Prabowo (Institut Teknologi Sepuluh Nopember, Indonesia)
- OS3-4            **Numerical and Experimental Investigation of Atomized Droplets Ejected from the Edge of a Rotating Disk**  
10:00-10:15      Akira Ishimaru, Shintaro Aihara (SCREEN Holdings Co., Ltd, Japan), Takeshi Matsuda (SCREEN Holdings Co., Ltd / Nagoya Institute of Technology, Japan), Masakazu Muto, Shinji Tamano (Nagoya Institute of Technology, Japan), Norimasa Matsui (SCREEN Holdings Co., Ltd, Japan)
- OS3-5            **Numerical Study of Extensional Characteristics of Liquid Ligament from the Edge of a Rotating Disk**  
10:15-10:30      Yuji Kawaguchi (Nagoya Institute of Technology, Japan), Akira Ishimaru, Shintaro Aihara (SCREEN Holdings Co., Ltd, Japan), Takeshi Matsuda (Nagoya Institute of Technology / SCREEN Holdings Co., Ltd, Japan), Masakazu Muto (Nagoya Institute of Technology, Japan), Norimasa Matsui (SCREEN Holdings Co., Ltd, Japan), Shinji Tamano (Nagoya Institute of Technology, Japan)
- 10:30-10:45      BREAK
- OS3-6            **Emerging Plasma Nanotechnology That Breaks Through the Limitations of Plasma Processing =Neutral Beam Atomic Layer Processing=** (*Invited*)  
10:45-11:15      Seiji Samukawa (National Yang Ming Chiao Tung University, Taiwan)
- OS3-7            **Evaluation of Thermal and Carrier Diffusion Properties of Si-Nanopillar/SiGe Composite Films by Laser Heterodyne Photothermal Displacement Method with Controlled Probe and Excitation Positions**  
11:15-11:30      Shota Urano, Yuta Hosokoshi (University of Miyazaki, Japan), Daisuke Ohori, Kazuhiko Endo (Tohoku University, Japan), Seiji Samukawa (Tohoku University, Japan / National Yang Ming Chiao Tung University, Taiwan), Atsuhiko Fukuyama (University of Miyazaki, Japan)

- OS3-8  
11:30-11:45 **Effect of Ligands of Amino Silane Precursors on SiO<sub>2</sub> Growth**  
Yuki Tsuchiizu (Tohoku University, Japan), Teruhisa Otsuka, Masashi Yamazaki (National Institute of Advanced Industrial Science and Technology (AIST), Japan), Daisuke Ohori (Tohoku University, Japan), Hiroshi Arimoto (National Institute of Advanced Industrial Science and Technology (AIST), Japan), Kazuhiko Endo (Tohoku University, Japan)
- OS3-9  
11:45-12:00 **Plasmonic Coupling-Driven Spectral Engineering in Metal Nanostructure-Integrated Light-Emitting Devices**  
Takayuki Kiba, Keisuke Ikeda, Midori Kawamura (Kitami Institute of Technology, Japan), Akio Higo (The University of Tokyo, Japan), Daisuke Ohori, Kazuhiko Endo (Tohoku University, Japan)
- OS3-10  
12:00-12:15 **Evaluation of Surface Roughening for Si(110) Ultrathin Nanosheet Transistor Channel**  
Yukinori Morita (National Institute of Advanced Industrial Science and Technology (AIST), Japan)
- OS3-11  
12:15-12:30 **Underlying Perspectives of Positive Temperature Dependence of Photoluminescence Peak Energy in Quantum Structures and Localized States of Semiconductors**  
Tetsuo Ikari (University of Miyazaki, Japan), Daisuke Ohori (Tohoku University, Japan), Atsuhiko Fukuyama (University of Miyazaki, Japan)